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a driver connected to the actuator to drive the actuator in response to detection results of the detector to suppress a strain of the holder resulting from a resonance of the projection system.

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18. (Twice Amended) A method of making an exposure apparatus that exposes a pattern onto a substrate, the method comprising:

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- providing a projection system to project the pattern onto the substrate;
- providing a holder connected to the projection system to hold the projection system;
- providing a main frame that mounts the projection system by means of the holder;
- providing a detector to detect information concerning displacement of the projection system;
- providing an actuator on the holder; and
- providing a driver connected to the actuator to drive the actuator in response to detection results of the detector to suppress a strain of the holder resulting from a resonance of the projection system.

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30. (Amended) A method of exposing a pattern onto a substrate through a projection system, the method comprising:

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- holding the projection system with a holder;
- mounting the projection system to a main frame by means of the holder;
- detecting information concerning displacement of the projection system; and
- driving an actuator mounted on the holder in response to the detected information to suppress a strain of the holder resulting from a resonance of the projection system.

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Please add new claims 45-51 as follows:

--45. (New) An exposure apparatus that exposes a pattern onto a substrate, the exposure apparatus comprising:

a projection system to project the pattern onto the substrate;

a support member to support the projection system;

a detector to detect information concerning displacement of the projection system;

an actuator arranged on the support member; and

a driver connected to the actuator in response to a detection result of the detector to suppress an influence of resonance of the projection.--

--46. (New) The exposure apparatus of claim 45, wherein the driver suppresses a strain of the support member.--

--47. (New) The exposure apparatus of claim 45, wherein the support member comprises a flange.--

--48. (New) The exposure apparatus of claim 45, wherein the actuator includes piezoelectric elements.--

--49. (New) The exposure apparatus of claim 45, wherein the detector is arranged on at least one of the projection system and the support member.--

--50. (New) The exposure apparatus of claim 45, wherein the detector includes an acceleration sensor.--

--51. (New) The exposure apparatus of claim 45, wherein the detector includes a distortion sensor.--

#### REMARKS

Claims 1-51 are pending. By this Amendment, claims 1, 18 and 30 are amended, and claims 45-51 are added. No new matter has been added. Reconsideration in view of the